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In re Application of

SCHUSTER

Application Number:

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Page No. 8

I hereby request access under 37 CFR 1.14(a)(1)(iv) to the application file record of the above-identified ABANDONED application, which is identified in, or to which a benefit is claimed, in the following document (as shown in the attachment):

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(19) **United States**(12) **Patent Application Publication** (10) Pub. No.: **US 2003/0007253 A1**  
Schuster et al. (43) Pub. Date: **Jan. 9, 2003**(54) **LARGE-APERTURED PROJECTION LENS  
WITH MINIMAL DIAPHRAGM ERROR**Nov. 30, 1998 (DE)..... 198 55 157.6  
May 14, 1999 (DE)..... 199 22 209.6  
Apr. 9, 1999 (DE)..... 199 42 281.8(76) Inventors: **Karl-Heinz Schuster, Königsbronn  
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09235, filed on Nov. 27, 1999.(30) **Foreign Application Priority Data**

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(57) **ABSTRACT**

The invention relates to a large-apertured microlithography projection lens. The diaphragm error is also systematically corrected, so that the pupil plane is slightly curved and the lens can be stopped down without comprising quality. The system diaphragm of the projection lens is located in the area of the last lens cluster of positive refractive power on the image side. The telecentrics of the projection lens remain stable on the image side during stopping down.

